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PPLICATION NO	. F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/617,679		07/14/2003	Wen-Chueh Pan	PANW3002/EM	4127
23364	7590	08/23/2004		EXAMINER	
BACON &	CON & THOMAS, PLLC SHAKERI, HAI				
625 SLATI				ART UNIT	PAPER NUMBER
FOURTH FLOOR			ARTUNII	PAPER NUMBER	
ALEXANDRIA, VA 22314				3723	

DATE MAILED: 08/23/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	7
	10/617,679	PAN ET AL.	/
Office Action Summary	Examiner	Art Unit	
	Hadi Shakeri	3723	
The MAILING DATE of this communication	n appears on the cover sheet w	ith the correspondence addre	ess
Period for Reply			
A SHORTENED STATUTORY PERIOD FOR R THE MAILING DATE OF THIS COMMUNICAT Extensions of time may be available under the provisions of 37 C after SIX (6) MONTHS from the mailing date of this communicati If the period for reply specified above is less than thirty (30) days If NO period for reply is specified above, the maximum statutory Failure to reply within the set or extended period for reply will, by Any reply received by the Office later than three months after the earned patent term adjustment. See 37 CFR 1.704(b).	ON. FR 1.136(a). In no event, however, may a on. , a reply within the statutory minimum of thir period will apply and will expire SIX (6) MON statute, cause the application to become Al	reply be timely filed ty (30) days will be considered timely. NTHS from the mailing date of this comn BANDONED (35 U.S.C. § 133).	nunication.
Status			
1) Responsive to communication(s) filed on			
	This action is non-final.		
3) Since this application is in condition for al		ters, prosecution as to the m	erits is
closed in accordance with the practice un			
Disposition of Claims			
4)⊠ Claim(s) <u>1-8</u> is/are pending in the applica	tion.		
4a) Of the above claim(s) is/are wit	hdrawn from consideration.		
5) Claim(s) is/are allowed.			
6)⊠ Claim(s) <u>1-8</u> is/are rejected.		•	
7) Claim(s) is/are objected to.			
8) Claim(s) are subject to restriction a	and/or election requirement.		
Application Papers		; <i>t</i>	
위한 (그) 20 등을 하였다. 그런, 물차 만드고 그 그 모든			
9) The specification is objected to by the Exa	·		
10)⊠ The drawing(s) filed on 14 July 2003 is/are			
Applicant may not request that any objection t			4 404415
Replacement drawing sheet(s) including the c			
11)☐ The oath or declaration is objected to by t	ne Examiner. Note the attache	d Office Action or form PTO-	152.
Priority under 35 U.S.C. § 119		:	
12)⊠ Acknowledgment is made of a claim for fo	reign priority under 35 U.S.C. 8	S 119(a)-(d) or (f).	
a)⊠ All b) Some * c) None of:		3 7 . 5 (2) (2) 5. (1)	
1.⊠ Certified copies of the priority docu	ments have been received.		
2. Certified copies of the priority docu		application No.	
3. Copies of the certified copies of the			age
application from the International B		•	•
* See the attached detailed Office action for		received.	
지어 마음 가는 살이 되었다면 그 그 그 살을			
Attachment(s)			
Notice of References Cited (PTO-892)	4) Interview	Summary (PTO-413)	
2) Notice of Neterellos Gled (170-532) Notice of Draftsperson's Patent Drawing Review (PTO-94)	8) Paper No(s)/Mail Date	
3) Information Disclosure Statement(s) (PTO-1449 or PTO/S	SB/08) 5) U Notice of I	nformal Patent Application (PTO-15	52)
Paper No(s)/Mail Date	6) 🔲 Other:	·	

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DETAILED ACTION

Claim Rejections - 35 USC § 112

- 1. The following is a quotation of the second paragraph of 35 U.S.C. 112:
 - The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.
- 2: Claims 4-8 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.
- 3. Regarding claims 4,and 6-8, the language as written renders the claims indefinite. The claims are generally narrative and indefinite, failing to conform with current U.S. practice. They appear to be a literal translation into English from a foreign document and are replete with grammatical and idiomatic errors. It is unclear what is being claimed by, e.g., "...abrasion is worked by that apply cavitation generated by scanning..."; "...abrasion is worked by that apply the ultrasonic waves to a pad to enable said pad to drive...". It also noted that it appears that no further steps are recited only what would naturally follow the step of applying ultrasonic "abrasion" or wave.

Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

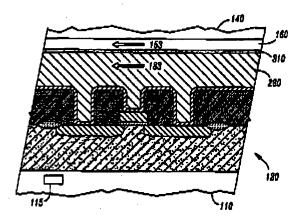
A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 5. Claims 1-8 as best understood are rejected under 35 U.S.C. 102(b) as being anticipated by Maury et al. (6,051,500).

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Maury et al. discloses all of the limitations of claim 1, i.e., a method of polishing metal and barrier layer interconnect integrated with an extremely low dielectric constant material, said method comprising the steps of: (a) preparing a wafer composed of a copper layer (260) and the extremely low dielectric constant material (220), said copper layer being



positioned over the low dielectric constant material, a barrier layer (250) being positioned between said copper layer and said low dielectric constant material; (b) treating said copper layer chemically (i.e., oxidizing the conductive material, col. 5, line 58) to produce a hard and brittle surface residue layer on the surface of said copper layer; (c) applying ultrasonic abrasion (i.e., producing ultrasonic vibration by polishing the first layer) to said surface residue layer to cause the brittle fracturing of said surface residue layer, thereby rendering effective polishing of said wafer; (d) applying the ultrasonic abrasion to said barrier layer (i.e., producing ultrasonic vibration by polishing the second layer) to render effective polishing of said wafer.

Regarding claims 2-8 (as best understood), Maury et al. meets the limitations, e.g., cuprous oxide; pad (160); transversal waves.

Claim Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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7. Claims 1-8 as best understood are rejected under 35 U.S.C. 102(b) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Symersky (3,822,467) in view of Sato (5,688,364).

Symersky discloses all of the limitations of claim 1, e.g., CMP polishing method of a metal and barrier layer with the use of ultrasonic vibration, col. 8, line 35, however, in the alternative. Sato is cited.

Sato teaches the use of ultrasonic vibration to CMP polishing of different layers of semiconductor devices. It would have been obvious to one of ordinary skill in the art, at the time the invention was made, to modify the invention of Symersky with ultrasonic abrasion for all layers as taught by Sato to enhance the polishing rate (Sato col. 6, line 25).

Regarding claims 2-8 as best understood, Symersky in view of Sato meets the limitations, metal oxide (skin or oxidation removal in CMP); different types of waves (Sato col. 8, line 20).

Conclusion

8. Prior art made of record and not relied upon are considered pertinent to applicant's disclosure. Ye et al., Shih et al. and Li et al. are cited to show related inventions.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hadi Shakeri whose telephone number is 703-308-6279. The examiner can normally be reached on Monday-Thursday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Joseph J. Hail, III can be reached on 703-308-2687. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Hadi Shakeri

Primary Examiner Art Unit 3723

August 18, 2004